



1201.64722

PATENT APPLICATION

#8
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10/9/02

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Li et al.)
Serial No.: 09/662,682)
Filed: September 15, 2000)
For: METAL-ASSISTED CHEMICAL)
ETCH POROUS SILICON)
FORMATION METHOD)
Art Unit: 1765)
Examiner: Vinh, Lan)

I hereby certify that this paper is being deposited with the United States Postal Service as FIRST-CLASS mail in an envelope addressed to: Assistant Commissioner for Patents, Washington, D.C. 20231, on this date.

Oct. 2, 2002 Chy B R
Date Registration No. 43,874
F-CLASS.WCM
Appr. February 20, 1998 Attorney for Applicant

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RESPONSE B

Assistant Commissioner for Patents
Washington, D.C. 20231

Dear Sir:

In response to the Office Action mailed August 2, 2002, which has been made final, please consider the following Remarks.

REMARKS

Claims 1-7, 9, 10-17, 19, and 20 stand rejected under 35 U.S.C. § 103(a) as being unpatentable over Russell in view of Yoshikawa. Claims 8 and 18 stand rejected under 35 U.S.C. §103(a) as being unpatentable over Russell in view of Yoshikawa, and further in view of Yamagata. Claim 21 stands rejected under 35 U.S.C. §103(a) as being unpatentable over Russell in view of Yoshikawa. Applicants respectfully traverse the rejection.